

## CLAIMS

1. A method of manufacturing a plasma display panel, in which a structure of the plasma display panel is formed with photolithography,  
5 wherein at least one of the structures of the plasma display panel is exposed twice in a process of forming the structure, and a photomask is moved within an allowable range of displacement in a exposure pattern, between a first and a second exposures.
- 10 2. A method of manufacturing a plasma display panel, in which a structure of the plasma display panel is formed with photolithography, wherein at least one of the structures of the plasma display panel is exposed twice in a process of forming the structure, and a photomask is moved by at least one cycle of periodicity included in a exposure pattern,  
15 and also within an allowable range of displacement at the position, between a first and a second exposures.